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**Art Unit: 1756**

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**From : Winston Hsu, Registration No. 41,526**

**Serial No.: 10/711,198**

**Attorney Docket No.: NAUP0493USA4**

**Subject: Information Disclosure Statement (IDS)**

**Total Pages: 81 pages (including cover page)**

**Winston Hsu 2005/11/24**

**NAUP0493USA4\_D1\_3**

PTO/SB/21 (09-04)

Approved for use through 07/31/2006. OMB 0651-0031

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<b>TRANSMITTAL FORM</b>  (to be used for all correspondence after initial filing)	Application Number	10/711,198	
	Filing Date	09/01/2004	
	First Named Inventor	Jiunn-Ren Hwang	
	Art Unit	1756	
	Examiner Name	YOUNG, CHRISTOPHER G	
Total Number of Pages in This Submission	80	Attorney Docket Number	NAUP0493USA4

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ENCLOSURES (Check all that apply)		
<input checked="" type="checkbox"/> Fee Transmittal Form	<input type="checkbox"/> Drawing(s)	<input type="checkbox"/> After Allowance Communication to TC
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**SIGNATURE OF APPLICANT, ATTORNEY, OR AGENT**

Firm Name	North America Intellectual Property Corporation		
Signature	<i>Winston Hsu</i>		
Printed name	Winston Hsu		
Date	11/24/2005	Reg. No.	41,526

**CERTIFICATE OF TRANSMISSION/MAILING**

I hereby certify that this correspondence is being facsimile transmitted to the USPTO or deposited with the United States Postal Service with sufficient postage as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on the date shown below:

Signature	<i>Cindy Lin</i>		
Typed or printed name	Cindy Lin	Date	11/24/2005

This collection of information is required by 37 CFR 1.5. The information is required to obtain or retain a benefit by the public which is to file (and by the USPTO to process) an application. Confidentiality is governed by 35 U.S.C. 122 and 37 CFR 1.11 and 1.14. This collection is estimated to 2 hours to complete, including gathering, preparing, and submitting the completed application form to the USPTO. Time will vary depending upon the individual case. Any comments on the amount of time you require to complete this form and/or suggestions for reducing this burden, should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, U.S. Department of Commerce, P.O. Box 1450, Alexandria, VA 22313-1450. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

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PTO/SB/17 (12-04)

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Effective on 12/08/2004. Fees pursuant to the Consolidated Appropriations Act, 2005 (H.R. 4818). <b>FEE TRANSMITTAL</b> <b>For FY 2005</b>		<b>Complete If Known</b>	
<input type="checkbox"/> Applicant claims small entity status. See 37 CFR 1.27		Application Number	10/711,198
<b>TOTAL AMOUNT OF PAYMENT</b> (\$) 0.00		Filing Date	09/01/2004
		First Named Inventor	Jiunn-Ren Hwang
		Examiner Name	YOUNG, CHRISTOPHER G
		Art Unit	1756
		Attorney Docket No.	NAUP0493USA4

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**FEE CALCULATION**

**1. BASIC FILING, SEARCH, AND EXAMINATION FEES**

Application Type	FILING FEES		SEARCH FEES		EXAMINATION FEES		Fees Paid (\$)
	Fee (\$)	Small Entity Fee (\$)	Fee (\$)	Small Entity Fee (\$)	Fee (\$)	Small Entity Fee (\$)	
Utility	300	150	500	250	200	100	
Design	200	100	100	50	130	65	
Plant	200	100	300	150	160	80	
Reissue	300	150	500	250	600	300	
Provisional	200	100	0	0	0	0	

**2. EXCESS CLAIM FEES**

Fee Description	Fee (\$)	Small Entity Fee (\$)
Each claim over 20 or, for Reissues, each claim over 20 and more than in the original patent	50	25
Each independent claim over 3 or, for Reissues, each independent claim more than in the original patent	200	100
Multiple dependent claims	360	180

**Total Claims**      **Extra Claims**      **Fee (\$)**      **Fee Paid (\$)**      **Multiple Dependent Claims**  
 - 20 or HP = \_\_\_\_\_ x \_\_\_\_\_ = \_\_\_\_\_  
 HP = highest number of total claims paid for, if greater than 20

**Indep. Claims**      **Extra Claims**      **Fee (\$)**      **Fee Paid (\$)**  
 - 3 or HP = \_\_\_\_\_ x \_\_\_\_\_ = \_\_\_\_\_  
 HP = highest number of independent claims paid for, if greater than 3

**3. APPLICATION SIZE FEE**

If the specification and drawings exceed 100 sheets of paper, the application size fee due is \$250 (\$125 for small entity) for each additional 50 sheets or fraction thereof. See 35 U.S.C. 41(a)(1)(G) and 37 CFR 1.16(s).

Total Sheets	Extra Sheets	Number of each additional 50 or fraction thereof	Fee (\$)	Fee Paid (\$)
- 100 = _____	/ 50 = _____	(round up to a whole number) x _____	= _____	

**4. OTHER FEE(S)**

	Fees Paid (\$)
Non-English Specification, \$130 fee (no small entity discount)	
Other: submission of Information Disclosure Statement	0.00

<b>SUBMITTED BY</b>			
Signature	<i>Winston Hsu</i>	Registration No. 41,526 (Attorney/Agent)	Telephone 302-729-1562
Name (Print/Type)	Winston Hsu	Date	11/24/2005

This collection of information is required by 37 CFR 1.136. The information is required to obtain or retain a benefit by the public which is to file (and by the USPTO to process) an application. Confidentiality is governed by 35 U.S.C. 122 and 37 CFR 1.14. This collection is estimated to take 30 minutes to complete, including gathering, preparing, and submitting the completed application form to the USPTO. Time will vary depending upon the individual case. Any comments on the amount of time you require to complete this form and/or suggestions for reducing this burden, should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, U.S. Department of Commerce, P.O. Box 1450, Alexandria, VA 22313-1450. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

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**PATENT****IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicants: Jiunn-Ren Hwang, Jui-Tsen Huang, Chang-Jyh Hsieh

5 Filing Date: 09/01/2004

Art Unit: 1756

Serial No.: 10/711,198

Docket No.: NAUP0493USA4

Examiner: YOUNG, CHRISTOPHER G

10 Confirmation No.: 5197

Title: OPTICAL PROXIMITY CORRECTION METHOD

To: Commissioner for Patents

15 P.O. BOX 1450

Alexandria, VA 22313-1450

Subject: Information disclosure statement under 37 C.F.R. §1.56.

20

Dear Sir:

This is an Information Disclosure Statement in accordance with the  
duty to disclose information material to patentability under 37 CFR  
25 §1.56. The applicant wishes to make of record the document(s) listed on  
the accompanying form PTO/SB/08.

Since this IDS is filed after the mailing date of the first Office action  
but before final Office action, consideration of the information  
30 disclosure statement is hereby requested according to 37 CFR §1.97(c).

That each item of information contained in the information

disclosure statement was first cited in an Office communication mailed on 2005/09/20 for the counterpart Japan patent application No. 2003-132557, which are no more than three months prior to the filing of the information disclosure statement.

5

According to the requirement set forth in 37 C.F.R. §1.98 and M.P.E.P. 609, the applicants are submitting a copy of the cited reference (Japan patents publication No. 11-102063, 5-19446, and 6-266095) and their English language abstracts hereinafter.

10

The abstract of the application (Japan patents publication No. 11-102063) is hereby presented to fulfill the information disclosure statement requirement set forth in 37 C.F.R. §1.98 and M.P.E.P. 609. The English language abstract of the application (Japan patents publication No. 11-102063) is listed as follows:

15

#### PROBLEM TO BE SOLVED:

To improve the transfer accuracy of intricate and fine patterns formed on an optical mask by patterning the phase shift film on a mask substrate to the shapes resembling the plane shape with the circuit patterns to be formed on a semiconductor wafer or the inversion patterns thereof.

20

#### SOLUTION:

Metallic layers 3 are patterned and formed to prescribed shapes on the main surface of the mask substrate 2 constituting a mask 1a. The original picture of integrated circuit patterns is composed of light shielding regions A and transmission regions B. The one transmission region B comprises a part coated with a transparent film (a) and a part not formed with this transparent film 4a. At the time of exposure, a phase difference of 180° is induced between the phase of the light transmitted through the transparent film 4a out of the light which is cast on the mask 1a and is transmitted through the one transmission region B

30

and the phase of the light transmitted through the ordinary transmission regions B. These light rays weaken each other in the boundary parts between the light shielding regions A and the transmission regions B and, therefore, unsharpness is reduced.

5

The abstract of the application (Japan patents publication No. 5-19446) is hereby presented to fulfill the information disclosure statement requirement set forth in 37 C.F.R. §1.98 and M.P.E.P. 609. The English language abstract of the application (Japan patents publication  
10 No. 5-19446) is listed as follows:

**PURPOSE:**

To provide the reduction stepping method which allows exposing of diversified and fine patterns in the process for production of the  
15 semiconductor device or semiconductor integrated circuit device.

**CONSTITUTION:**

This method consists in executing reduction stepping by using a phase shift mask provided with prescribed correction patterns 101b at the ends  
20 of a mask pattern region of a specified mode or in the boundary parts of the mask pattern regions of plural modes. Since an end effect, etc., are offset by the correction patterns, the exposing of the diversified and fine patterns is executed.

25 The abstract of the application (Japan patents publication No. 6-266095) is hereby presented to fulfill the information disclosure statement requirement set forth in 37 C.F.R. §1.98 and M.P.E.P. 609. The English language abstract of the application (Japan patents publication No. 6-266095) is listed as follows:

30

**PURPOSE:**

To eliminate a defect generated from the non-uniformity of a thin layer

of chromium of a damping phase shift type reticle.

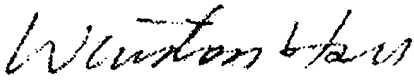
CONSTITUTION:

5 This reticle 20 is provided with a secondary resolution pattern 22 in an  
area other than a graphic part to be formed. By the secondary resolution  
pattern 22, the radiation light of practically uniform and attenuated  
intensity is transmitted. By the graphic part, phase shift is performed to  
the secondary resolution pattern 2 as the following. That is, the phase of  
light passed through the graphic parts is shifted for about 180° to the  
10 phase of the radiation light passed through the secondary resolution  
pattern 2 surrounding the graphic parts and attenuated.

15

Respectfully submitted,

20



Date: November 24, 2005

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25

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Note: Please leave a message in my voice mail if you need to talk to me. (The time in  
D.C. is 13 hours behind the Taiwan time, i.e. 9 AM in D.C. = 10 PM in Taiwan.)